

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Li, et al.
App. No.	:	Unknown
Filed	:	Herewith
For	:	ELIMINATION OF DENDRITE FORMATION DURING METAL/CHALCOGENIDE GLASS DEPOSITION
Examiner	:	Unknown
Group Art Unit	:	Unknown

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Enclosed are copies of forms PTO-1449 and 892 listing 29 references. These references are of record in related application No. 10/164,429, filed June 6, 2002. Therefore, copies of the references are not enclosed. This Information Disclosure Statement is being filed upon filing, and no fee is required in accordance with 37 C.F.R. § 1.97(b)(1).

Identification herein is not an admission that any of the foregoing references are prior art to the above-captioned application.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated:

June 24, 2003

By:



Michael S. Okamoto  
Registration No. 47,831  
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FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. MICRON.2003 25DC1	APPLICATION NO. <del>2003-00000000</del> Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT	APPLICANT Li, et al.	FILING DATE June 6, 2003 June 24, 2003
(USE SEVERAL SHEETS IF NECESSARY)	GROUP 2003 Unknown	COPY

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
		6,348,365	02/19/02	Moore, et al.			
		6,418,049	07/09/02	Kozicki, et al.			

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EXAMINER	DATE CONSIDERED
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FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MICRON.250A 250CI	APPLICATION NO. 10404,046 Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT Li, et al.	GROUP 2000 Unknown
(USE SEVERAL SHEETS IF NECESSARY)		FILING DATE June 6, 2002 June 24, 2003	

COPY

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
	6,487,106	11/26/02	Kozicki			
	2002/0168820	11/14/02	Kozicki, et al.			
	2002/0190350	12/19/02	Kozicki, et al.			
	2003/0035314	02/20/03	Kozicki			
	2003/0035315	02/20/03	Kozicki			
	2003/0048519	03/13/03	Kozicki			

## FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)	

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040903

EXAMINER	DATE CONSIDERED
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	

<b>Notic of References Cited</b>	Application/Control No.	Applicant(s)/Patent Under Reexamination
	10764,546 Unknown	LI ET AL
	Examiner	Art Unit
	DUNIGAN Unknown	2848 Unknown

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	COPY	Classification
✓	A	US-2002/0123248	✓ 03-2001	Moore et al.		438/795
✓	B	US-4,115,872	✓ 09-1978	Bluhm, Vernon A.		257/2
	C	US-				
	D	US-				
	E	US-				
	F	US-				
	G	US-				
	H	US-				
	I	US-				
	J	US-				
	K	US-				
	L	US-				
	M	US-				

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. MICRON 250A 250C1	APPLICATION NO. 10/602,040 Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT	
(USE SEVERAL SHEETS IF NECESSARY)		Li, et al.	
		FILING DATE June 6, 2002	GROUP Unknown

**COPY**

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EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME		CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
	5,761,115	6/2/1998	Kozicki, et al.				
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	6,084,796	07/04/00	Kozicki, et al.				
	10/164,429	06/06/02	Li, et al.				

FOREIGN PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	WO 00/48196	08/17/00	WO				
	WO 02/21542 A1	03/14/02	WO				

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)
	P. Boolchand, et al., "Mobile Silver Ions and Glass Formation in Solid Electrolytes" <u>Nature</u> , Vol. 410, April 2001, pp. 1070-1073
	Y. Hirose, et al., "High Speed Memory Behavior and Reliability of an Amorphous As2S3 Film Doped With Ag" <u>Physica Status Solidi</u> Vol. (a), No. 16, (1980) K187-K190
	Y. Hirose, et al., "Polarity-Dependent Memory Switching and Behavior of Ag Dendrite in Ag-Photodoped Amorphous As2-s3 Films" <u>J. Appl. Phys.</u> Vol. 47, No. 6, June 1976 pp. 2767-2772
	A. V. Kolobov, et al., "Photodoping of Amorphous Chalcogenides by Metals" <u>Advances in Physics</u> 1991, Vol. 40, No. 5, pp. 625-684
	M. Mitkova, et al., "Dual Chemical Role of Ag as an Additive in Chalcogenide Glasses" <u>Physical Review Letters</u> Vol. 83, No. 19, pp. 3748-3851
	K. L. Tai, et al., "Bilevel High Resolution Photolithographic Technique For Use With Wafers Stepped and/or Reflecting Surfaces" <u>J. Vac. Sci. Technol.</u> Vol. 16, No. 6, Nov/Dec 1979 pp. 1977-1979
	K. L. Tai, et al., "Inorganic Resist Systems for VLSI Microlithography" pp. 9-35
	K. L. Tai, et al., "Submicron Optical Lithography Using an Inorganic Resist/Polymer Bilevel Scheme" <u>J. Vac. Sci. Technol.</u> Vol. 17, No. 5, Sept/Oct 1980 pp. 1169-1176
	A. Yoshikawa, et al., "Angstroms Resolution in Se-Ge Inorganic Photoresists" <u>Japanese Journal of Applied Physics</u> Vol. 20, No. 2, Feb. 1981, pp. L81-L83
	A. Yoshikawa, et al., "Dry Development of Se-Ge Inorganic Photoresist" <u>Appl. Phys. Lett.</u> Vol 36, No. 1, Jan. 1980, pp. 107-109
	A. Yoshikawa, et al., "A New Inorganic Electron Resist of High Contrast" <u>Appl. Phys. Lett.</u> Vol. 31, No. 3, Aug. 1977, pp. 161-163
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*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	